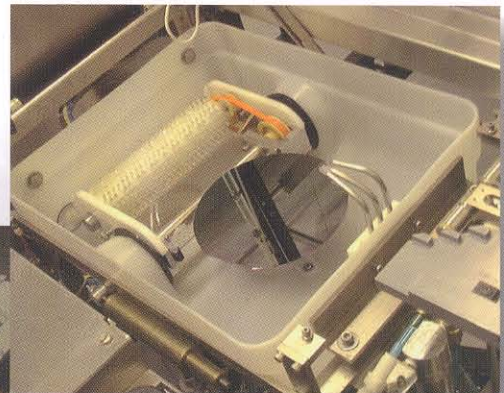
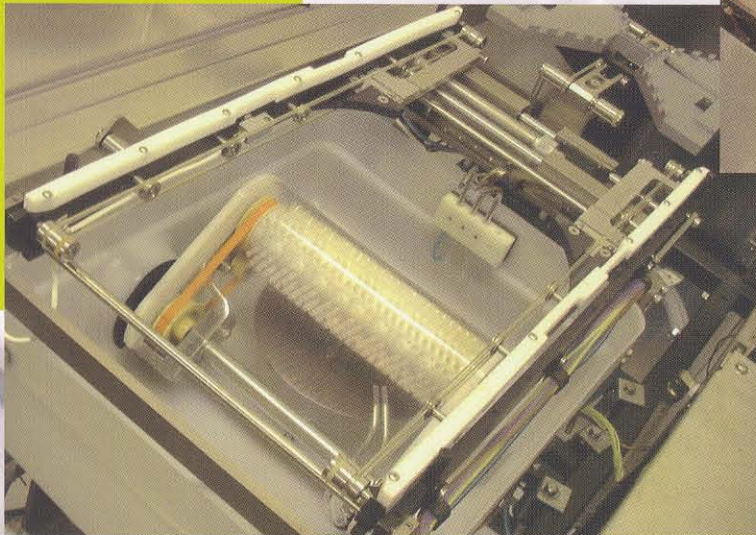




## SCRUBBER (WAFER CLEANER)

The SVG\* 86 and 88 series SSC (single sided cleaner) scrubbers clean 2" to 150mm wafers with a brush scrub and/or high pressure metal lift-off. Both series of scrubber systems have flexible process options for ease of use and improved process capability.

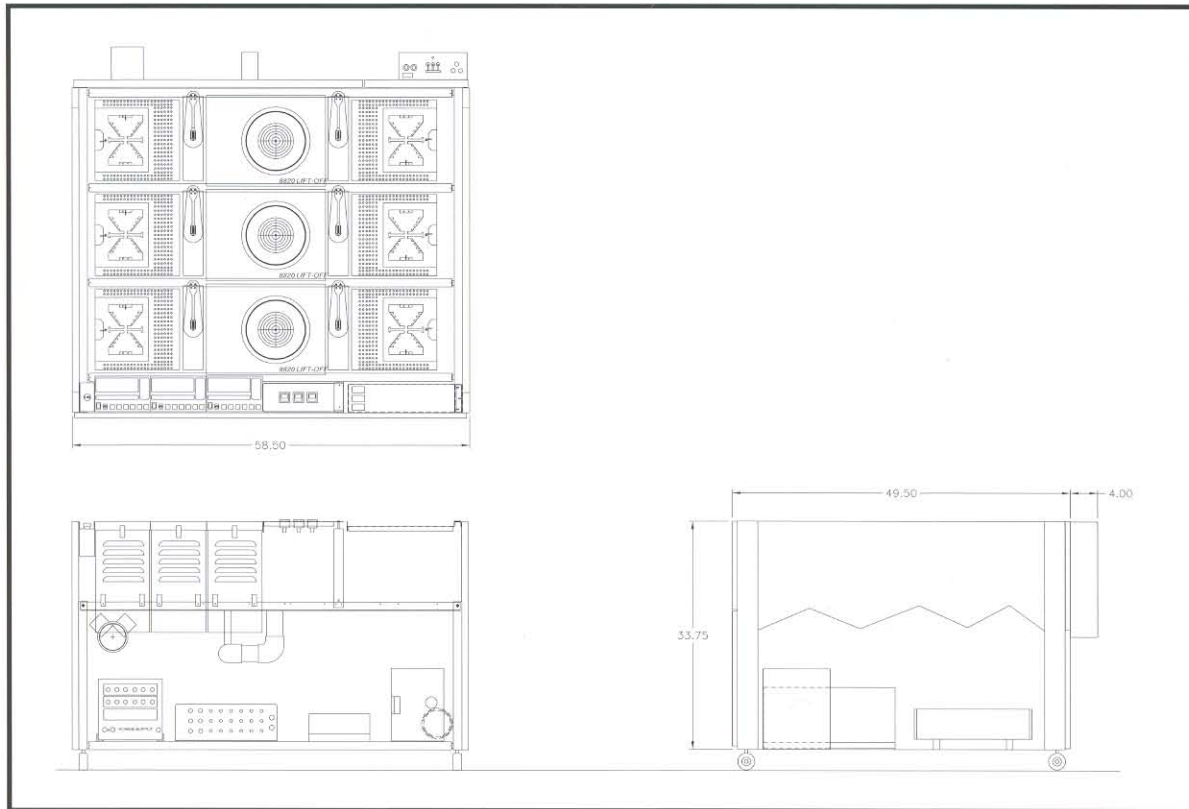
Mission Technology Inc. provides remanufacturing and upgrades of both series of single sided cleaning systems. In addition to restoring the interior and exterior aspects of the system, we also enhance the system with upgraded parts and/or modules, which have been tested rigorously in the field. Several example of these components are listed below:



**IMPROVED AIR RINGS** keep the wafer and the chuck completely dry during processing.

**ADJUSTABLE HIGH PRESSURE NOZZLE** provides better coverage of the full wafer diameter during each cleaning cycle, and reduces static build-up.

# SCRUBBER (WAFER CLEANER)



CONFIGURATION DRAWING SHOWN IN 88XX SERIES

CATEGORY	FEATURE	SPECIFICATION	FACILITY REQUIREMENTS
SYSTEM BASIC	WAFER SIZE	3"-6" WAFERS (100MM - 150MM)	POWER 208 VAC, 3 PHASE, 15A (DIFFERENT VOLTAGE/PHASE COMBINATION POSSIBLE)
	USER INTERFACE / CONTROLLER	CARD CAGE	
VAPOR PRIME	TEMPERATURE RANGE	50 - 250°C ±0.5°C (50-150°C), ±0.5% (151-250°C)	
CHILL PLATE	TEMPERATURE RANGE	18.0 - 30°C ±0.1°C WITH CHILLER (IDLE AT AMBIENT)	N <sub>2</sub> 80 PSI CDA 80 PSI EXHAUST 2.5 INCH H <sub>2</sub> O VACUUM 30 INCH HG DI WATER 25 PSI PCW 17°C (± 2°C)
HPO	TEMPERATURE RANGE	50 - 250°C ±0.5°C (50-150°C), ±0.5% (151-250°C)	
SCRUBBER	MAXIMUM SPIN SPEED	6000 RPM (WITH 6" WF), 8500 RPM (WITHOUT WF)	
	SPIN SPEED ACCURACY	≤ 2 RPM	
	ACCELERATION RANGE	0-50000 RPM / SEC.	
	CHUCK TEMP. UNIFORMITY	≤ 0.2 °C ACROSS SPIN CHUCK	
	BRUSH SPEED	100 - 600 RPM IN 1 RPM INCREMENT	
	BRUSH FORCE	ADJUSTABLE FROM 0 TO 2 LBS	
	HIGH PRESSURE ARM SWEEP	PROGRAMMABLE FROM 25 TO 99 CYCLES PER MINUTE	
	SWEEP NOZZLE PRESSURE	LOW PRES.: 400 - 1400 PSI, HIGH PRES.: 1400 - 5000 PSI	
WAFER TRANSFER	ATS TRANSFER ARM		
PARTICLE LEVEL	≤ 100 PARTICLES @ 0.2 μm, WITH PRIME TEST WAFERS		
RELIABILITY	MTBF	≥200 HOURS	
	MTBA	≥50 HOURS	
	MWBF	≥10,000 WAFERS	
	MWBA	≥2,000 WAFERS	
	UPTIME	≥95%	
WAFER BREAKAGE	≤1 IN 10,000 WAFERS		
SAFETY	TEFLON WIRING	STANDARD	
	SOLVENT PLUMBING	TEFLON OR S.S.	
	SPILL CONTAINER IN CABINET	CUSTOM	
	EXHAUSTED CABINET	OPTION	

